

Amendments to the Specification

Please amend paragraph [0050] on page 15 as follows:

[0050] Projection radially inner sidewalls 50 can be considered as having an elevational length B. In the depicted Fig. 4 embodiment, recess outer peripheral sidewall 42 and radially inner sidewall 50 have a combined elevational length C which is equal to the thickness of substrate 41 for which the susceptor is designed. Additionally, upper surface 52 has an uppermost elevation, or point, 53 which is received elevationally higher than substrate 41 for which the susceptor is designed, when ~~susceptor~~ substrate 41 rests on base 44.

Please amend paragraph [0054] on page 17 as follows:

[0054] Referring again to Fig. 4, projection upper surface 52 is depicted as extending along a straight line in ~~radially~~ radial cross-section, although curved lines (i.e., convex or concave) are also contemplated but not preferred. In the illustrated preferred embodiment, projection upper surface 52 is angled radially downward toward substrate receiving recess 40 and along a straight line in radial cross-section, as shown. Where at least one of face portion 46 and base 44 are substantially planar, upper surface 52 is preferably angled at from 20° to 80° from the respective face portion and/or base, and more preferably at from 40° to 60°. An exemplary angle of 40° is shown in Figs. 4 and 5 for surface 52, and also 40° for surface 52d in Fig. 8 (described below). An angle of 20° is shown in Figs. 6 and 7 for surfaces 52b and 52c.

Please amend paragraph [0055] on page 17 as follows:

[0055] Fig. 8 depicts an alternate exemplary embodiment susceptor 30d. Like numerals from the first described embodiment are utilized where appropriate, with differences being indicated with the suffix "d" or with different numerals. Susceptor 30d comprises a projection 48d comprising a radially inner sidewall 50d extending outwardly from recess outer peripheral sidewall 42 to a projection upper surface 52d. At least a portion of ~~outer peripheral~~ radially inner sidewall 50d is angled radially downward toward substrate receiving recess 40. Specifically, recess ~~outer peripheral~~ radially inner sidewall 50d includes a first portion 55 extending perpendicular relative to recess base 44, and a second portion 58 extending from ~~first portion 56~~ first portion 55 and being angled radially downward toward substrate receiving recess 40. In preferred embodiments, surfaces 52, 52a, 52b, 52c and 58 extend along a line in radial cross-section such that the surfaces have a radial extent (i.e., an x-axis dimension "X" of the angle formed by such surfaces

with surface portion 46 and/or base 44) of at least 5 millimeters.

Please amend paragraph [0062] on page 21 as follows:

[0062] Fig. 10 depicts back side face 64 ~~comprising a multiple~~ comprising multiple radiation emission-lowering recesses 72 received opposite a portion of front side inner area face 70 in the form of annular grooves. Such grooves are of a common shape and square in cross-section, as depicted. In the depicted preferred embodiment, back side face 64 is substantially planar but for said radiation emission-lowering recesses 72. Further, body 61 has a constant thickness H within at least a majority of, and within all of as shown, inner area face 70 over which substrate 71 to be deposited upon is to be received but for said radiation emission-lowering recesses 72.

Please amend paragraph [0065] on page 22 as follows:

[0065] Each of the above-described Figs. 9-13 preferred embodiments show a plurality of discrete radiation emission-lowering recesses which are continuously formed about an annulus. By way of example only, Fig. 14 depicts a plurality of discrete half-spherical radiation emission-lowering recesses 72d formed about an annulus. Positioning other than about an annulus is also of course contemplated.